L Number	Hits	Search Text	DB	Time stamp
1	124	(((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/09/01 15:51
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	, ,
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic) and magnet	IBM_TDB	
2	11	(((((((((exposure adj apparatus) and lithography) and	USPAT;	2004/09/01 15:54
		(stage or table)) and (mask or reticle)) and illumination) and	US-PGPUB;	200,,00,01
!		(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
]		and electromagnetic) and magnet) and (driver or mover))	IBM_TDB	
1		and stator) and (magnetic adj pole)	1011_100	
_	2492	(exposure adj apparatus) and lithography	USPAT;	2004/09/01 15:50
	2152	(exposure adj apparatus) and hatography	US-PGPUB;	2001/05/01 15:50
			EPO; JPO;	
			IBM_TDB	
1	1852	((exposure adj apparatus) and lithography) and stage	USPAT;	2004/02/18 16:29
-	1032	((exposure adj apparatus) and ildiography) and stage	US-PGPUB;	2004/02/10 10.23
			EPO; JPO;	
			IBM_TDB	
_	1783	(((exposure adj apparatus) and lithography) and stage) and	USPAT;	2004/02/18 16:29
] -	1763	(((exposure adj apparatus) and indiography) and stage) and (mask or reticle)	US-PGPUB;	2004/02/10 10.23
1		(mask of fedcle)	EPO; JPO;	
			IBM_TDB	
	2134	((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:29
-	2134	table)	US-PGPUB;	2004/02/10 10.23
i		(able)	EPO; JPO;	
			IBM_TDB	
_	2020	(((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:29
-	2020	table)) and (mask or reticle)	US-PGPUB;	2007/02/10 10.23
		(mask of feticle)	EPO; JPO;	
			IBM_TDB	
_	1362	((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:30
-	1302	table)) and (mask or reticle)) and illumination	US-PGPUB;	2004/02/10 10.30
		table)) and (mask of redde)) and marmination	EPO; JPO;	
			IBM_TDB	
_	1342	(((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/24 15:15
	1342	table)) and (mask or reticle)) and illumination) and (wafer or	US-PGPUB;	200 1/02/21 13:13
		specimen or sample)	EPO; JPO;	•
		specimen of sample)	IBM_TDB	
	170	((((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:32
	170	table)) and (mask or reticle)) and illumination) and (wafer or	US-PGPUB;	2001/02/10 10:52
		specimen or sample)) and (reaction near4 force)	EPO; JPO;	
		opening of outtipley) and (reading) float (float)	IBM_TDB	
] _	206	(((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:32
		table)) and (reaction near4 force)	US-PGPUB;	,,
[EPO; JPO;	
]			IBM_TDB	
1 -	118	(((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/18 16:32
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
<u> </u>		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic	IBM_TDB	
-	100	(((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/09/01 15:51
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic) and magnet	IBM_TDB	
-	9	((((((((((((((((((((((((((((((((((((((USPAT;	2004/09/01 15:52
		(stage or table)) and (mask or reticle)) and illumination) and	US-PGPUB;	
		(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
		and electromagnetic) and magnet) and (driver or mover))	IBM_TDB	
		and stator) and (magnetic adj pole)	_	

-	24	((((((((exposure adj apparatus) and lithography) and	USPAT;	2004/02/24 15:14
		(stage or table)) and (mask or reticle)) and illumination) and	US-PGPUB;	
		(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
		and electromagnetic) and magnet) and (driver or mover)) and stator	IBM_TDB	
-	56	((((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/24 13:54
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic) and magnet) and (driver or mover)	IBM_TDB	
-	5	((((((((exposure adj apparatus) and lithography) and	USPAT;	2004/02/24 13:55
		(stage or table)) and (mask or reticle)) and illumination) and	US-PGPUB;	
		(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
		and electromagnetic) and magnet) and (driver or mover)) and canceling	IBM_TDB	
-	6	((((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/24 15:25
		table)) and (mask or reticle)) and illumination) and (wafer or	US-PGPUB;	
		specimen or sample)) and (reaction adj cancel\$3)	EPO; JPO;	
			IBM_TDB	